

| L Number | Hits | Search Text | DB | Time stamp |
|----------|-------|---|---|------------------|
| 1 | 55654 | (silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:24 |
| 2 | 1364 | (silicon near oxide or "Sio.sub.2") same (oxygen near plasma) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 14:39 |
| 3 | 1148 | ((silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3)) and ((silicon near oxide or "Sio.sub.2") same (oxygen near plasma)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 14:40 |
| 4 | 52 | ((silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3)) and ((silicon near oxide or "Sio.sub.2") same (oxygen near plasma))) and (ion near5 (inert near gas or argon)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 14:41 |
| 5 | 16 | ((silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3)) and ((silicon near oxide or "Sio.sub.2") same (oxygen near plasma))) and (ion near5 (inert near gas or argon))) and @pd<19990507 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 16:19 |
| 6 | 1894 | ((oxygen near plasma) or ashing) same (silicon near oxide or "Sio sub.2") | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 16:24 |
| 7 | 1515 | ((oxygen near plasma) or ashing) same (silicon near oxide or "Sio sub.2")) same (etch\$3 or remov\$3) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 16:29 |
| 8 | 695 | ((oxygen near plasma) or ashing) same (silicon near oxide or "Sio sub.2")) same (etch\$3 or remov\$3)) and @pd<19990507 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 16:30 |
| 9 | 167 | ((oxygen near plasma) or ashing) same (silicon near oxide or "Sio.sub.2")) same (etch\$3 or remov\$3)) and @pd<19990507) and (argon or (inert near gas)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 16:51 |
| 10 | 72 | (native near oxide) same (oxygen near plasma) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:05 |
| 11 | 30 | ((native near oxide) same (oxygen near plasma)) and @pd<19990507 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:08 |
| 12 | 16 | (silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3) and (((native near oxide) same (oxygen near plasma)) and @pd<19990507) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:14 |
| 13 | 7 | (silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3) and (((native near oxide) same (oxygen near plasma)) and @pd<19990507) and argon | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:15 |

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| 14 | 324 | ((silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3 or clean\$3) and 134/1.1-1.3.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:27 |
| 15 | 117 | ((silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3 or clean\$3) and 134/1.1-1.3.ccls.) and (ion near argon or "Ar"or sputter\$3) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:30 |
| 16 | 52 | ((silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3 or clean\$3) and 134/1.1-1.3.ccls.) and (ion near argon or "Ar"or sputter\$3)) and @pd<19990507 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:34 |
| 17 | 2 | ((silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3 or clean\$3) and 134/1.1-1.3.ccls.) and (ion near argon or "Ar"or sputter\$3)) and @pd<19990507 and ((silicon near oxide or "Sio.sub.2") same (oxygen near plasma)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:36 |
| 18 | 31 | ((silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3)) and ((silicon near oxide or "Sio.sub.2") same (oxygen near plasma))) and 438/723.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:37 |
| 19 | 11 | ((silicon near oxide or "Sio.sub.2") same (remov\$3 or etch\$3)) and ((silicon near oxide or "Sio.sub.2") same (oxygen near plasma))) and 438/723.ccls.) and @pd<19990507 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/12/04 17:38 |